

SUPPORT FOR THE AMENDMENT

This Amendment amends Claim 1 and adds new Claims 15-18. Support for the amendments is found in the specification and claims as originally filed. In particular, support for Claim 1 is implicit in Claim 10 and in the specification at page 19, lines 9-17, and page 20, lines 7-10 (i.e., the disclosure "[i]t is possible to perform mechanical surface roughening (such as sand blasting) on the glass-like carbon tube ... in an environment for chemical surface roughening (for example, in an environment for thermal oxidation). ... The treatment for chemical surface roughening includes thermal oxidation ..." implies that the entire surface of the component is roughened). Support for new Claim 15 is found in Claims 1 and 12. Support for new Claim 16 is found in Claim 1 and Fig. 1. Support for new Claim 17 is found in Claims 1 and 12. Support for new Claim 18 is found in the specification at least at page 8, lines 9-11. No new matter would be introduced by entry of these amendments.

Upon entry of these amendments, Claims 1-18 will be pending in this application. Claims 1 and 16 are independent. Claims 5-14 are withdrawn from consideration.

REQUEST FOR RECONSIDERATION

Applicants respectfully request entry of the foregoing and reexamination and reconsideration of the application, as amended, in light of the remarks that follow.

Applicants thank the Examiner for courtesies extended to the representative during the October 6, 2005, personal interview.

As discussed at the personal interview, the present invention provides a component of glass-like carbon for a CVD apparatus. Because the component is roughened over its entire surface and then purified to remove metal impurities, contamination from CVD deposits flaking off of the component is reduced. The purification step can be at high temperatures in a halogen-containing gaseous atmosphere. Preferably, surface roughening of the component

is performed on all sides simultaneously so as to minimize dimensional changes caused by the purification step. If surface roughening is performed on the inner and outer sides of a tube separately, comparatively large stresses occur during the purification step, and this makes it difficult to obtain an inner tube with sufficient roundness for a CVD apparatus (although the reason for this is not known). Specification at page 7, lines 2-14; page 8, lines 16-18; page 19, lines 9-17.

Claims 1 and 4 are rejected under 35 U.S.C. § 103(a) over U.S. Patent No. 6,383,333 ("Haino") in view of U.S. Patent No. 5,993,596 ("Uwai"). In addition, Claims 2 and 3 are rejected under 35 U.S.C. § 103(a) over Haino and Uwai and further in view of U.S. Patent No. 5,324,411 ("Ichishima").

Haino discloses a hollow, protection member 2 arranged along the inner wall of a plasma processing apparatus. The hollow, inner wall protection member 2 is formed of a glass-like carbon material and has an average surface roughness on its *inner surface* of 2.0 μm or less. Haino discloses that the inner surface of the protection member is gradually worn out by reaction with corrosive gas during plasma processing and that if the average surface roughness exceeds 2.0 μm , then the inner surface of the protection member 2 may fall off as particles depending on wear conditions. Haino at Abstract; Fig. 1; column 2, lines 42-44; 53-55; column 3, lines 17-18; 47-54; column 4, lines 35-36; 62; column 6, lines 53-56.

However, Haino fails to suggest the limitation of independent Claims 1 and 16 of a component having a value of surface roughness (Ra), *over the entire surface of the component*, ranging from 0.1 to 10 μm (measured according to JIS B0601).

Furthermore, because the outer wall of Haino's protection member 2 is adjacent to the inner wall of the plasma processing apparatus and not exposed to plasma, Haino is not concerned with the roughness of the outer wall of protection member 2. Thus, there is no reasonable expectation that the skilled artisan would have been led by Haino to successfully

reach the feature of independent Claims 1 and 16 of a component having a value of surface roughness (Ra), *over the entire surface of the component*, ranging from 0.1 to 10 μm (measured according to JIS B0601).

The secondary references fail to remedy the deficiencies of Haino. Uwai is cited for disclosing a component for plasma processing having a reduced metal impurity content. Office Action at page 3, section 7. Ichishima is cited for disclosing a glass-carbon component having porosity. Office Action at page 3, section 13.

Because the cited art fails to suggest all the limitations of independent Claims 1 and 16, the prior art rejection should be withdrawn.

Pursuant to M.P.E.P. § 821.04, after independent product Claim 1 is allowed, Applicants respectfully request rejoinder, examination and allowance of withdrawn process Claims 5-12, which include all of the limitations of product Claim 1.

In view of the foregoing amendments and remarks, Applicants respectfully submit that the application is in condition for allowance. Applicants respectfully request favorable consideration and prompt allowance of the application.

Should the Examiner believe that anything further is necessary in order to place the application in even better condition for allowance, the Examiner is invited to contact Applicants' undersigned attorney at the telephone number listed below.

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